

L Number	Hits	Search Text	DB	Time stamp
1	963764	oxide or dioxide or "sio.sub.2"	USPAT; US-PGPUB; JPO	2004/08/25 18:12
2	5448	(fluoride or fluorinate) adj3 ((oxide or dioxide or "sio.sub.2") or glass)	USPAT; US-PGPUB; JPO	2004/08/25 18:13
3	1649	fsg	USPAT; US-PGPUB; JPO	2004/08/25 18:13
4	7065	((fluoride or fluorinate) adj3 ((oxide or dioxide or "sio.sub.2") or glass)) or fsg	USPAT; US-PGPUB; JPO	2004/08/25 18:13
5	101847	(silicon adj nitride) or "si.sub.3 n.sub.4"	USPAT; US-PGPUB; JPO	2004/08/25 18:14
6	20456	(silicon adj oxynitride) or sion	USPAT; US-PGPUB; JPO	2004/08/25 18:14
7	201040	interconnection\$1 or metallization\$1	USPAT; US-PGPUB; JPO	2004/08/25 18:15
8	355382	etch\$3	USPAT; US-PGPUB; JPO	2004/08/25 18:15
9	194047	cmp or polish\$3	USPAT; US-PGPUB; JPO	2004/08/25 18:15
10	502	((((fluoride or fluorinate) adj3 ((oxide or dioxide or "sio.sub.2") or glass)) or fsg) and ((silicon adj nitride) or "si.sub.3 n.sub.4") and ((silicon adj oxynitride) or sion)	USPAT; US-PGPUB; JPO	2004/08/25 18:15
11	17340	((interconnection\$1 or metallization\$1) or damascen\$3) and etch\$3 and (cmp or polish\$3)	USPAT; US-PGPUB; JPO	2004/08/25 18:16
12	290	(((((fluoride or fluorinate) adj3 ((oxide or dioxide or "sio.sub.2") or glass)) or fsg) and ((silicon adj nitride) or "si.sub.3 n.sub.4") and ((silicon adj oxynitride) or sion)) and (((interconnection\$1 or metallization\$1) or damascen\$3) and etch\$3 and (cmp or polish\$3)))	USPAT; US-PGPUB; JPO	2004/08/25 18:16
13	212	(((((fluoride or fluorinate) adj3 ((oxide or dioxide or "sio.sub.2") or glass)) or fsg) and ((silicon adj nitride) or "si.sub.3 n.sub.4") and ((silicon adj oxynitride) or sion)) not (((fluoride or fluorinate) adj3 ((oxide or dioxide or "sio.sub.2") or glass)) or fsg) and ((silicon adj nitride) or "si.sub.3 n.sub.4") and ((silicon adj oxynitride) or sion)) and (((interconnection\$1 or metallization\$1) or damascen\$3) and etch\$3 and (cmp or polish\$3)))	USPAT; US-PGPUB; JPO	2004/08/25 18:16